

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L56	19	(exposure near (method or process)).clm. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and mask.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:05
L57	5	(exposure near (method or process)).clm. with (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and mask.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:04
L58	4	(exposure near (method or process)).clm. with (first adj alignment adj mark).clm. with (second adj alignment adj mark).clm. and mask.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:04
L59	3	(exposure near (method or process)).clm. with (first adj alignment adj mark).clm. with (second adj alignment adj mark).clm. with mask.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:04
L60	19	(exposure adj (method or process)).clm. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and mask.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:06
L61	5	(exposure adj (method or process)).clm. same (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and mask.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:06
L62	4	(exposure adj (method or process)).clm. same (first adj alignment adj mark).clm. same (second adj alignment adj mark).clm. and mask.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:06
L63	3	(exposure adj (method or process)).clm. same (first adj alignment adj mark).clm. same (second adj alignment adj mark).clm. same mask.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:06
L64	5	(exposure adj (method or process)).clm. with (first adj alignment adj mark).clm. same (second adj alignment adj mark).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:07

L65	5	(exposure adj (method or process)).clm. with (first adj alignment adj mark).clm. with (second adj alignment adj mark).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:07
L66	5	(exposure adj (method or process)).clm. same ((first adj alignment adj mark).clm. with (second adj alignment adj mark)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:08
L67	3	(exposure adj (method or process)).clm. same ((first adj alignment adj mark).clm. with (second adj alignment adj mark) with mask).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:08
L68	3	(exposure near(method or process)).clm. same ((first adj alignment adj mark).clm. with (second adj alignment adj mark) with mask).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:08
L69	3	(exposure near (method or process)).clm. same ((first adj alignment adj mark).clm. with (second adj alignment adj mark) with mask).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:09
L70	3	(exposure near2 (method or process)).clm. same ((first adj alignment adj mark).clm. with (second adj alignment adj mark) with mask).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:27
L71	4	(exposure near2 (method or process)).clm. same ((first adj alignment adj mark).clm. with (second adj alignment adj mark) with pattern).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/06 14:28